



0039-7632-0016

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF: :
HIROYUKI YANO ET AL : GROUP ART UNIT: 1765
SERIAL NO. 09/531,163 :
FILED: MARCH 17, 2000 : EXAMINER: DEO, D.

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Freda
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OCT 10 2001

TC 1700

FOR: AQUEOUS DISPERSION, AQUEOUS
DISPERSION FOR CHEMICAL
MECHANICAL POLISHING USED
FOR MANUFACTURE OF SEMI-
CONDUCTOR DEVICES, METHOD
FOR MANUFACTURE OF ...

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Responsive to the Office Action of July 5, 2001, Applicants respectfully request reconsideration of the above-identified application in view of the following amendments and remarks.

IN THE CLAIMS

Please cancel Claims 1-39. ✓

Please add new Claims 44-75 as follows:

44. (New) An aqueous dispersion for chemical mechanical polishing used in the manufacture of semiconductor devices, said dispersion comprising polymer particles, inorganic particles and water, wherein the zeta potential of said polymer particles and the